

<b>Notice of References Cited</b>	Application/Control No. 10/566,948		Applicant(s)/Patent Under Reexamination COSTA ET AL.	
	Examiner PETER RADKOWSKI		Art Unit 2883	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,078,516 A	01-1992	Kapon et al.	385/129
*	B	US-5,761,350 A	06-1998	Koh, Seungug	385/14
*	C	US-6,229,947 B1	05-2001	Vawter et al.	385/132
*	D	US-6,240,233 B1	05-2001	Weinert et al.	385/131
*	E	US-2002/0037025 A1	03-2002	Bartman et al.	372/50
*	F	US-6,396,984 B1	05-2002	Cho et al.	385/43
*	G	US-2002/0071914 A1	06-2002	Ouellet et al.	427/377
*	H	US-2003/0007766 A1	01-2003	Galarza et al.	385/132
*	I	US-2003/0059556 A1	03-2003	Ouellet et al.	427/569
*	J	US-2003/0235370 A1	12-2003	Taillaert et al.	385/50
*	K	US-2007/0130996 A1	06-2007	Ouellet et al.	065/384
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Baak, T.; "Silicon oxynitride; a material for GRIN optics;" 15 March 1982; Applied Optics, Vol. 21, No. 6; pp. 1069-72.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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